

# ELECTRONIC INFORMATION DISCLOSURE STATEMENT

Electronic Version v18

Stylesheet Version v18.0

## Title of Invention

HIGH-SPEED DIAPHRAGM VALVE FOR ATOMIC LAYER  
DEPOSITION

Application Number : 10/609134  
Confirmation Number: 6738  
First Named Applicant: Jarmo Maula  
Attorney Docket Number: 11429/13:1  
Art Unit:  
Examiner:  
Search string: ( 5520001 or 6752387 or 20030121608 ).pn



## US Patent Documents

Note: Applicant is not required to submit a paper copy of cited US Patent Documents

init	Cite.No.	Patent No.	Date	Patentee	Kind	Class	Subclass
KL	1	5520001	1996-05-28	Miyamoto et al.		62	50.2
KL	2	6752387	2004-06-22	Nishizato et al.	B1	261	62

## US Published Applications

Note: Applicant is not required to submit a paper copy of cited US Published Applications

init	Cite.No.	Pub. No.	Date	Applicant	Kind	Class	Subclass
KL	1	20030121608	2003-07-03	Chen et al.	A1	156	345.33

## Signature

Examiner Name	Date
Kevin Lee	5/7/05